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eu-LISA Selects Accenture, Atos and Safran to Enhance EU Visa Information and Biometric Matching Systems

The European Agency for the operational management of large-scale IT systems in the area of freedom, security and justice (eu-LISA) has selected Accenture (NYSE: ACN), Safran Identity & Security and Atos to provide application and infrastructure services for the E.U. Visa Information System (VIS) and for the Biometric Matching System (BMS) underpinning VIS.

TRAVEL

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The project will facilitate the fast and secure processing of visa applications by third country nationals requiring visas to enter the Schengen area. The Accenture-Safran-Atos consortium will help eu-LISA deliver new digital services to its customers around the world and enhance the capabilities of the VIS Mail system, which is used to exchange information between member-state authorities.

The contract, awarded following a call for tenders (LISA/2015/RP/02 VIS/BMS MWO) by eu-LISA, is for four years, with option for an extension of up to two years.

Accenture is excited to have been selected to help eu-LISA manage the safe and legitimate movement of people into the European Union... We will bring our significant experience managing large, complex IT-based identity-management projects for border-management and other government agencies around the world to help ensure the success of this mission-critical program for eu-LISA.

James Canham, managing director of Accenture's Customs & Borders business

As consortium leader, Accenture is responsible for overall program management, including delivering enterprise and technology architecture and design support, providing application development and maintenance services, and managing IT on-site service support functions. Safran will continue to develop the **biometric solution** and provide all biometric-related consulting services and expertise. Atos will be responsible for provision and maintenance of infrastructure solutions.

Atos is looking forward to enhancing our collaboration with eu-LISA by bringing our expertise in infrastructure managed services to support border management efforts in the E.U. With our proven experience in maintaining large-scale IT platforms, we will seek to ensure the corrective, adaptive and evolutive maintenance of VIS and its BMS infrastructure

to meet all user needs and system performance requirements.

Punit Sehgal, Atos group vice president and account lead for European institutions

Safran has worked with the European Commission since 2007 on the development and maintenance of the biometric matching engine at the heart of the EU's visa system. This contract is a continuation of our decade-long efforts to help the E.U. manage its borders. It leverages our deep expertise and understanding of the latest biometric technologies to support enhanced border management and border security in Europe.

Philippe Arnaud, VP and general manager of Safran's Border Control business

Learn more about Accenture's global Public Safety business and the company's work with border agencies.

About IDEMIA - OT-Morpho is now IDEMIA, the global leader in Augmented Identity for an increasingly digital world, with the ambition to empower citizens and consumers alike to interact, pay, connect, travel and vote in ways that are now possible in a connected environment.

Securing our identity has become mission critical in the world we live in today. By standing for Augmented Identity, we reinvent the way we think, produce, use and protect this asset, whether for individuals or for objects. We ensure privacy and trust as well as guarantee secure, authenticated and verifiable transactions for international clients from Financial, Telecom, Identity, Public Security and IoT sectors.
OT (Oberthur Technologies) and Safran Identity & Security (Morpho) have joined forces to form IDEMIA. With close to $3 billion in revenues and 14,000 employees around the world, IDEMIA serves clients in 180 countries.

For more information, head to www.idemia.com. And follow us @IdemiaGroup on Twitter.